

Materials List for:

# Fabrication of Flexible Image Sensor Based on Lateral NIPIN Phototransistors

Hyun Myung Kim<sup>\*1</sup>, Gil Ju Lee<sup>\*1</sup>, MinSeok Kim<sup>1</sup>, Young Min Song<sup>1</sup>

<sup>1</sup>School of Electrical Engineering and Computer Science, Gwangju Institute of Science and Technology

\*These authors contributed equally

Correspondence to: Young Min Song at [ymsong@gist.ac.kr](mailto:ymsong@gist.ac.kr)

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## Materials

Name	Company	Catalog Number	Comments
MBJ3	karl suss	MJB3 UV400 MASK ALIGNER	Mask aligner
80 plus RIE	Oxford instruments	Plasmalab 80 Plus for RIE	ICP-RIE
80 plus PECVD	Oxford instruments	Plasmalab 80 Plus for PECVD,	PECVD
SF-100ND	Rhabdos Co., Ltd.	SF-100ND	Spin coater
Polyimide	Sigma-Aldrich	575771	Poly(pyromellitic dianhydride-co-4,4'-oxydianiline), amic acid solution
SOI (silicon on insulator) wafer, 8inch	Soitec	SOI (silicon on insulator) wafer, 8inch	8inch SOI Wafer (silicon Thickness: 1.25µm)
Acetone	Duksan Pure Chemicals Co., Ltd.	3051	Acetone
Isopropyl Alcohol (IPA)	Duksan Pure Chemicals Co., Ltd.	4614	Isopropyl Alcohol (IPA)
Buffered Oxide Etch 6:1	Avantor	1278	Buffered Oxide Etch 6:1
HSD150-03P	Misung Scientific Co., Ltd	HSD150-03P	Hot plate
AZ5214	Microchemical	AZ5214	Photoresist
MIF300	Microchemical	MIF300	Developer
SYLGARD184	Dow Corning	SYLGARD184	Polydimethylsiloxane elastomer
Hydrofluoric Acid	Duksan Pure Chemicals Co., Ltd.	2919	Hydrofluoric Acid
CR-7	KMG Chemicals, Inc	210023	Chrome mask etchant
MFCD07370792	Sigma-Aldrich	651842	Gold etchant